Application of: Euijoon Yoon et al.

Serial No.: 10/596,126

Amendment after Non-Final Office Action

AMENDMENTS TO THE ABSTRACT

Please replace the Abstract with the following paragraph:

[Abstract]

The present invention relates to a growth method of nitride semiconductor layer eomprising a first step for growing Growing a first nitride 5 semiconductor layer on an

 $Al_xGa_vIn_{1-x-v}N(0 < x < 1, 0 < y < 1, 0 < x + y < 1)$ $Al_xGa_vIn_{1-x-v}N(0 \le x \le 1, 0 < y \le 1, 0 < x + y \le 1)$ layer, a

second step for reducing the thickness of the first nitride semiconductor layer by growth

interruption and, a third step for growing a second nitride semiconductor layer having a band gap

energy higher than that of the first nitride semiconductor layer on the first nitride semiconductor

layer with the [[to]] reduced thickness and a light emitting device using the growth method.